

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Mark Trulson et al.

Serial No: 09/922, 426

Filing Date: August 3, 2001

Title: **METHODS OF ARRAY  
SYNTHESIS**

Examiner: Baker, Maurie Garcia

Group Art Unit: 1639

INFORMATION DISCLOSURE  
STATEMENT

Mail Stop Issue Fee  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Applicants thank the Examiner for the Notice of Allowance received on this application. However, it has recently come to our attention that certain references were not cited to the Office. In an abundance of caution, Applicants hereby submit the enclosed RCE and an Information Disclosure Statement containing the references.

Pursuant to 37 CFR §§ 1.97-98, Applicants hereby submit the enclosed PTO form 1449. Copies of these references are enclosed. This Information Disclosure Statement is in compliance with the continuing duty of candor as set forth in 37 CFR § 1.56 and is being filed concurrently with a Request for Continued Examination (RCE) and before the mailing date of a first Office Action. Accordingly, no fee is due.

The references have not been reviewed in sufficient detail to make any representation regarding materiality and, in particular, no representation is intended as to the relative importance of any portion of the references. This statement is also not a representation that the listed references have effective dates early enough to be "prior art" within the meaning of 35 USC § 102 or § 103.

In view of the above disclosure, Applicants believe that the current application is in order for an expedited allowance.

If the Examiner has any questions, please call the undersigned at (408) 731-5000. Please apply any charges or credits to Deposit Account No. 01-0341.

Dated: 8/11/04

Respectfully submitted,

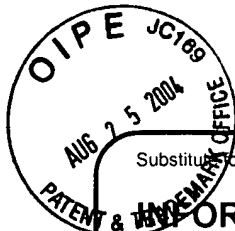
A handwritten signature in black ink, appearing to read 'T E Malone', written over a horizontal line.

Thomas E. Malone

Reg. No. 40,078

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STATEMENT BY APPLICANT**

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Sheet 2 of 3

**Complete if Known**

Application Number	09/922,426
Filing Date	August 3, 2001
First Named Inventor	Trulson et al.
Art Unit	1639
Examiner Name	Maurie Garcia Baker
Attorney Docket Number	3305.1

**NON PATENT LITERATURE DOCUMENTS**

Examiner Initials *	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	8	Griffing and West IEEE Electron Device Letters EDL-4(1): 14(1983).	
	9	GHANDI, VLSI Fabrication Principles, 1983, Chapter 10.	
	10	HOFER et al., Contrast enhanced uv lithography with polysilanes, Advances in Resist Technology, 1984, 108-16, SPIE Vol. 469.	
	11	HALLE, L., et al., J. Vac. Sci. Technol. B., 1985, 323-326, Vol. 3(1).	
	12	SHEATS, et al., SPIE Proc. 1986, 631, 171	
	13	UCHINE, et al., Proc. Poly. Mat. Sci. And Eng., 1986, 55, 604-607.	
	14	PAUL R. WEST, et al., Contrast Enhanced Photolithography: Application of Photobleaching Processes in Microlithography, J. Imaging Science, March/April 1986, 65-68, Vol. 30, No. 2.	
	15	DON R. STROM, Optical Lithography and Contrast Enhancement, Semiconductor International, May 1986, 162-67.	
	16	ENDO, et al., High aspect-ratio resist pattern fabrication by alkaline surface treatment, J. Vac. Sci. Technol. B., 1989, 1076-79, Vol. 7(5).	
	17	UCHINO, SHOU-ICHI et al., Synthesis of new metal-free diazonium salts and their applications to microlithography, Journal of Photopolymer Science and Technology (1989); 2 (1): 255-299.	
	18	REISER, et al., Photoreactive Polymers: the Science and technology of Resists, 1989, 226-29.	

Examiner  
SignatureDate  
Considered

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached. This collection of information is required by 37 CFR 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 120 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, U.S. Department of Commerce, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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	19	SALAMY, et al., Proc. Electrochem. Soc., 1989, 90:36.	
	20	DURAND, et al., Nucleic Acids Res., 1990, 6353-59, Vol 18., No. 21.	
	21	TOSHIHIKO TANAKA, et al., Sub-Halfmicron Lithography Using a High-Contrast i-Line CEL, Japanese J. Applied Physics, Sept. 1990, 1860-61, Vol. 29, No. 1.	
	22	R. PFORR, et al., Contrast enhancement of the resist latent image using exposure induced absorption amplification - fundamental, modeling, and applicability, Microelectronic Engineering, 1992, 321-326, Vol. 17.	
	23	DAVID M. TEEGARDEN, et al., Contrast Enhancement Lithography System Based on Pyrylium Dye Bleach Chemistry, J. Imaging Science and Technology, 1993, 149-155, Vol. 37, No. 2.	
	24	THOMPSON, L.F., et al., Introduction to Microlithography, America Chemical Society, 1994 212-232.	
	25	HUANG, Proc. SPIE - Int. Soc. Opt. Eng., 1999, 3678, (Pt. 2) 340-51.	
Examiner Signature		Date Considered	

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